

	Hit s	Search Text	DBs
12	0	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same cur\$4) and (cutter or cutt\$4) and (tack\$6) and (fold\$6) and ((resist or photoimageable or photoresist) same (liquid or ink) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4) same (carrier or sheet or transfer or (temporary near5 sheet))) same transparent same laminat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	0	430/311.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet))) same transparent same laminat\$4) and develop\$5 and cur\$3 and (cut\$5 or drill\$4) and fold\$6	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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14	0	430/330.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or drill\$4) and fold\$6	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	0	430/314.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or drill\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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16	0	216/18.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or drill\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	0	174/254.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or drill\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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18	0	29/825.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or drill\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	0	29/825.ccls. and ((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and (cur\$3 or heat\$4) and (cut\$5 or fold\$4 or tack\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB